

Ref. #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4479	438/300-305.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 14:16
L2	1152	257/382-384.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 14:17
L3	5529	1 2	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 14:17
L4	153	3 and (nitrogen near1 gas)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:31
L5	62	4 and wet	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 14:18
L6	28	5 and (photoresist (photo near resist))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:31
L7	20	6 and plasma	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:32
L8	33	("5817562").URPN.	USPAT	OR	ON	2004/12/08 14:44
L9	9	("4912061" "5102816" "5153145" "5254490" "5264391" "5286667" "5290720" "5378654" "5707901").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/08 15:28
L10	108065	(nitrogen near1 gas)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:31
L11	2072	10 and wet and (photoresist (photo near resist))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:31
L12	495	11 and plasma and source and drain and gate	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 18:08
L13	341	12 and substrate and dielectric	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 18:09
L14	341	13 and (method process)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:35
L15	88	14 and (metal near silicide)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 18:09
L16	8	15 and (ild (interlevel near dielectric))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:37

L17	5	15 and (contact near mask)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:37
L18	83	15 not 17	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:38
L19	20	18 and interconnection	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:39
L20	63	18 not 19	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:38
L21	18	18 and stop	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:50
L22	0	("6706640").URPN.	USPAT	OR	ON	2004/12/08 15:43
L23	4	("5269879" "5935877" "6117786" "6265271").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/08 15:49
L24	1	15 and borderless	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/08 15:49
L25	81	15 not 7	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/08 15:50
L26	18	25 and stop	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:51
L27	61	25 and (stop stopping barrier)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:53
L28	19	25 and (stop stopping)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:52
L29	1	27 and deionized	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 15:53
L30	1113	11 and plasma and source	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 18:08
L31	552	11 and plasma and source and drain	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 18:08
L32	341	12 and dielectric	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 18:09
L33	88	13 and (metal near1 silicide)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2004/12/08 18:09

L34	0	("6674135").URPN.	USPAT	OR	ON	2004/12/08 18:22
L35	7	("4654828" "5663570" "5856693" "5866460" "5908313" "5970352" "6004878").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/08 18:22